

IN THE CLAIMS

Please amend the claims as follows:

Claims 1-8 (Canceled).

Claim 9 (Currently Amended): An internal member of a plasma processing vessel, comprising:

a base material; and

a film formed on a surface of the base material,

wherein the film has a main layer formed by thermal spraying of ceramic and a barrier coat layer formed of ceramic including an element selected from the group consisting of B, Mg, Al, Si, Ca, Cr, Y, Zr, Ta, Ce and Nd,

wherein the barrier coat layer is an intermediate layer formed between the main layer and the base material, and

wherein the barrier coat layer is a thermally sprayed film and at least parts of pores inside the thermally sprayed film are sealed by a resin provided below a surface of the film and not provided on a surface of the main layer.

Claim 10 (Original): The internal member of claim 9, wherein the barrier coat layer is formed of at least one kind of ceramic selected from the group consisting of B₄C, MgO, Al₂O₃, SiC, Si₃N₄, SiO₂, CaF₂, Cr₂O₃, Y₂O₃, YF₃, ZrO₂, TaO₂, CeO₂, Ce₂O₃, CeF₃ and Nd₂O₃.

Claim 11 (Canceled).

Claim 12 (Previously Presented): The internal member of claim 9, wherein the resin is selected from the group consisting of SI (silicone), PTFE (polytetrafluoroethylene), PI

(polyimide), PAI (polyamideimide), PEI (polyetherimide), PBI (polybenzimidazole) and PFA (perfluoroalkoxyalkane).

Claim 13 (Canceled).

Claim 14 (Previously Presented): The internal member of claim 31, wherein the sealing treatment is executed by using an element of the Group 3a in the periodic table.

Claim 15 (Original): The internal member of claim 9, wherein the main layer is formed of at least one kind of ceramic selected from the group consisting of B_4C , MgO , Al_2O_3 , SiC , Si_3N_4 , SiO_2 , CaF_2 , Cr_2O_3 , Y_2O_3 , YF_3 , ZrO_2 , TaO_2 , CeO_2 , Ce_2O_3 , CeF_3 and Nd_2O_3 .

Claims 16-30 (Canceled).

Claim 31 (Previously Presented): The internal member of claim 9, wherein an anodic oxidized film is formed between the base material and the film, and

wherein at least parts of pores inside the anodic oxidized film are sealed by a second resin selected from the group consisting of SI (silicone), PTFE (polytetrafluoroethylene), PI (polyimide), PAI (polyamideimide), PEI (polyetherimide), PBI (polybenzimidazole) and PFA (perfluoroalkoxyalkane).

Claim 32 (Previously Presented): The internal member of claim 9, wherein an anodic oxidized film is formed between the base material and the film, and pores in the anodic oxidized film are sealed by an aqueous solution of metal salt.

Claims 33-37 (Canceled).

Claim 38 (Previously Presented): The internal member of claim 31, wherein the main layer is formed of at least one kind of ceramic selected from the group consisting of B_4C , MgO , Al_2O_3 , SiC , Si_3N_4 , SiO_2 , CaF_2 , Cr_2O_3 , Y_2O_3 , YF_3 , ZrO_2 , TaO_2 , CeO_2 , Ce_2O_3 , CeF_3 and Nd_2O_3 .